

Please revise the first paragraph as follows:

--This application is a continuation-in-part of U.S. Application No. 09/491,969, filed January 27, 2000, which claims the benefit of U.S. Application No. 60/117,671, filed January 28, 1999, and is a continuation-in-part of U.S. application No. 09/261,475, filed February 26, 1999 (now U.S. Patent No. 6,404,107), which is a continuation-in-part of U.S. Application No. 08/943,645, filed October 3, 1997 (now U.S. Patent No. 6,069,433), which is a continuation of U.S. Application No. 08/188,145, filed January 27, 1994 (now U.S. Patent No. 6,420,819), the disclosures of each of which are hereby incorporated by reference.--

Please revise the abstract as follows:

--A multi-input, multi-output vibration control system for a lithography system. The system provides an actuator, and a sensor useful for controlling vibrations in systems for fabricating electronics equipment. The system includes a processor programmed with a multi-input, multi-output control technique such as a linear quadratic Gaussian, H-infinity or mu synthesis. The actuator may comprise one or more plates or elements of electroactive material bonded to an electroded sheet.--

#### IN THE CLAIMS:

Please amend Claim 1 as follows:

1. (Amended) A motion control system for use with a lithography system, said motion control system comprising:
  - a wafer stage base;
  - at least two actuators for controlling motion;
  - at least two sensors for detecting at least one parameter of displacement of said wafer base and producing at least two signals in response thereto; and
  - at least one circuit in electrical communication with said actuators and said sensors;wherein said circuit comprises a computer processor programmed with a multi-input, multi-output control technique selected from the following group of control techniques: linear

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